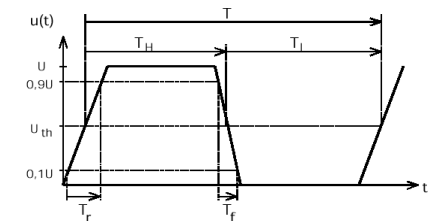
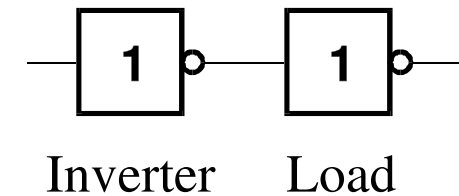
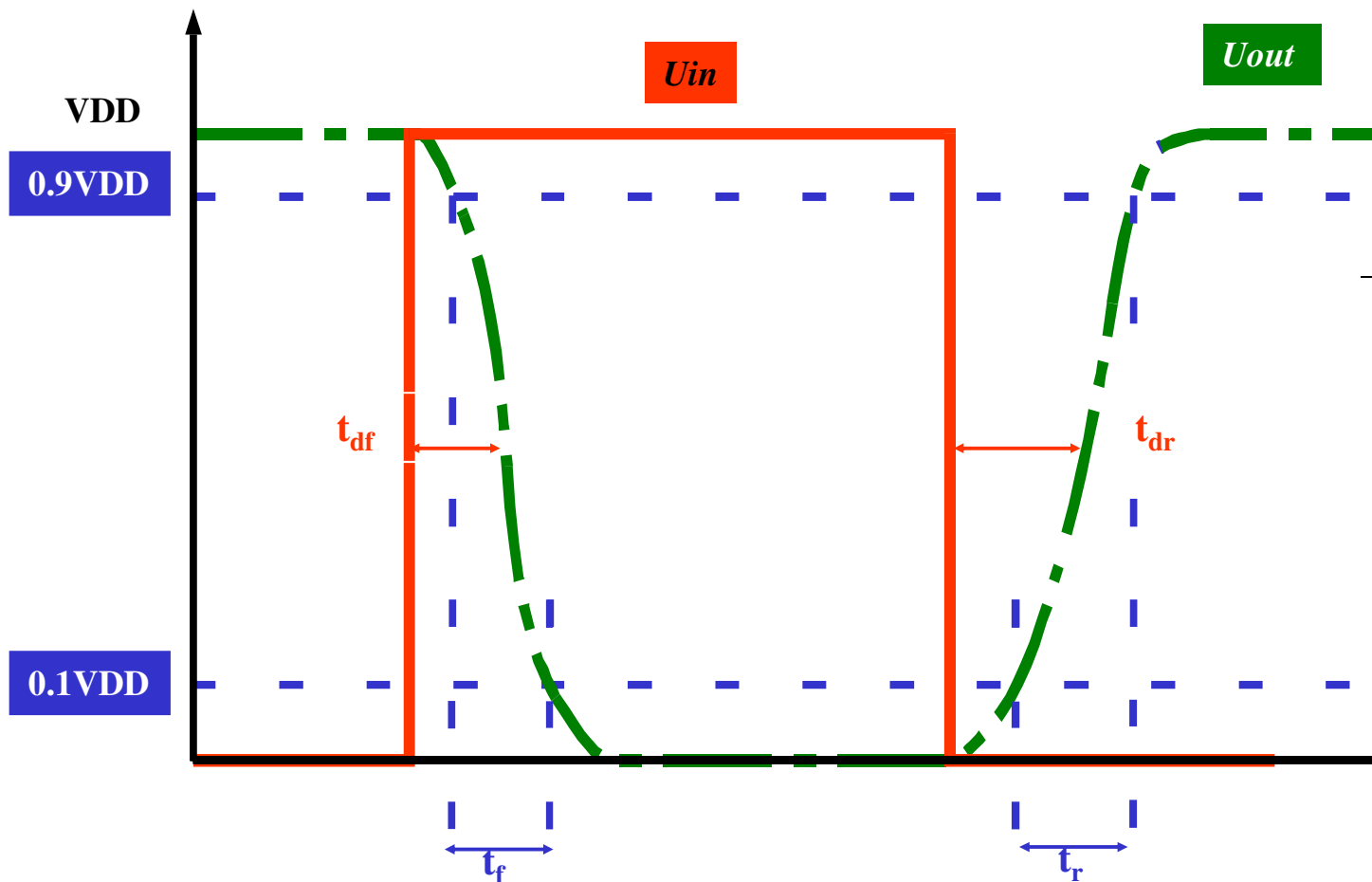
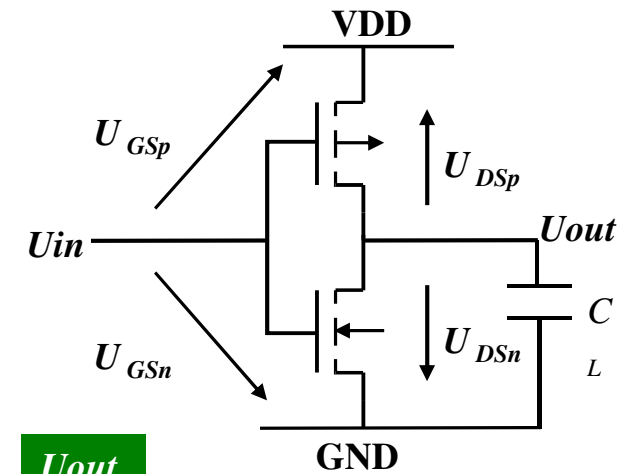


# Chapter 4 Contents

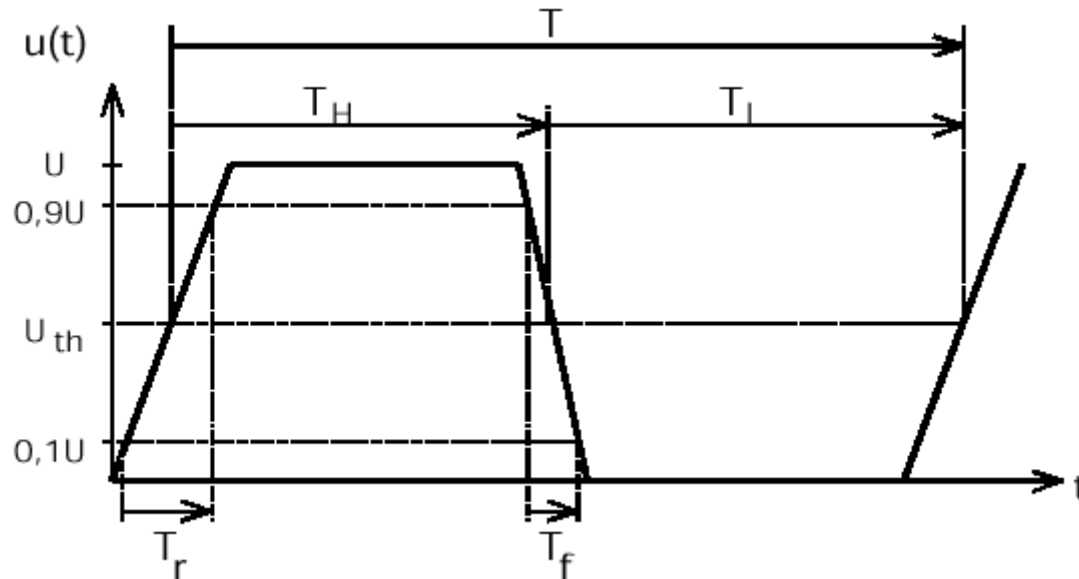
- Introduction in digital circuitry
- Digital MOS-circuits
- CMOS - complementary MOS
- Pseudo-NMOS (p-channel-transistor as load)
- **Delays**
- **Power Consumption**

# Definition of delay times

Charging of a load (capacity) via inverter



# Simplified representation of a pulse signal



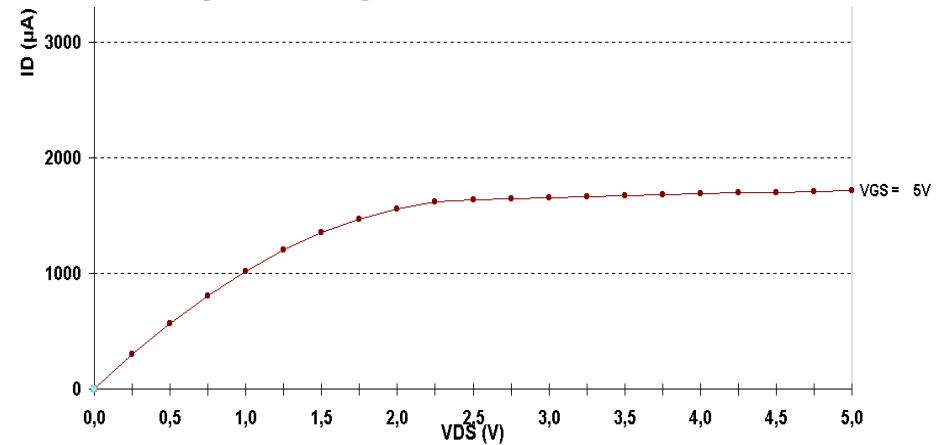
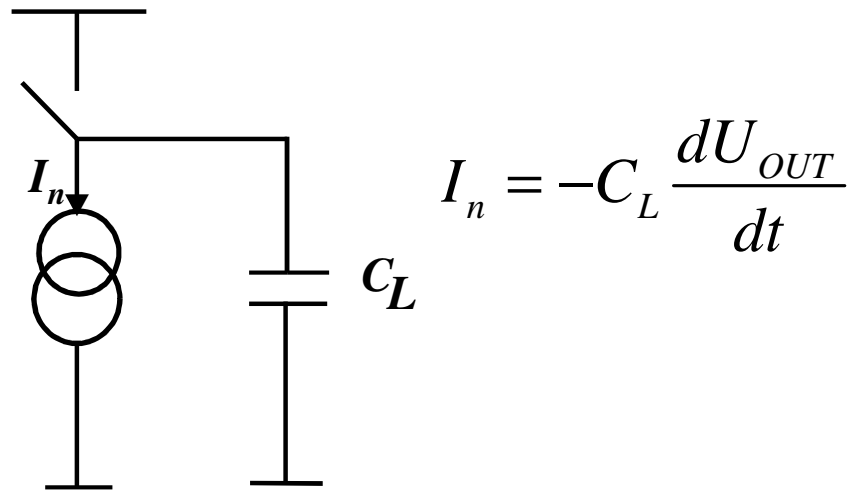
$U < 0.1 \cdot U_{DD} = \text{Low} \quad (U_{TN} = 0.2 \cdot U_{DD})$

$U > 0.9 \cdot U_{DD} = \text{High} \quad (U_{TP} = 0.2 \cdot U_{DD})$

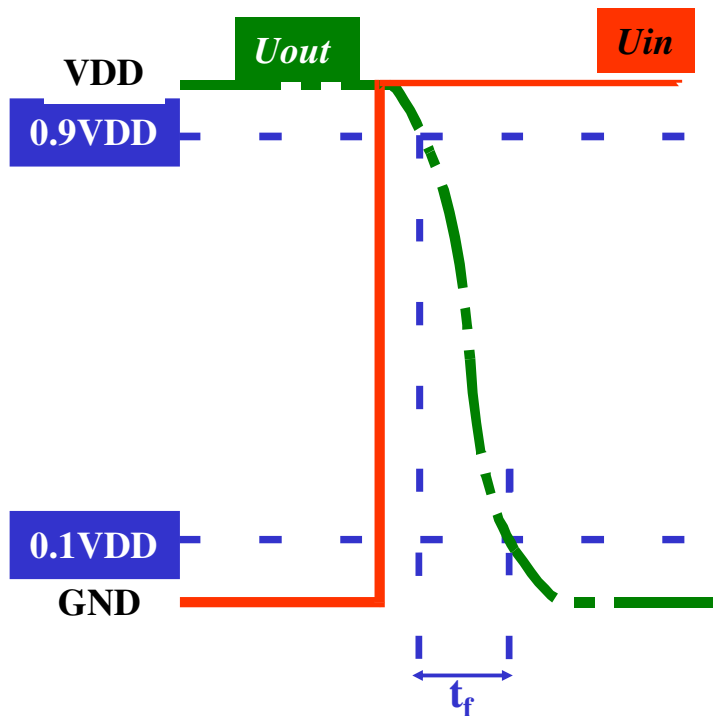
Period from  $U = 0.1 \cdot U_{DD}$  to  $0.9 \cdot U_{DD}$ :  $T_R$  (rise time)

Period from  $U = 0.9 \cdot U_{DD}$  to  $0.1 \cdot U_{DD}$ :  $T_F$  (fall time)

# Delay times (Falling Edge)



$$t_f = \int_{t_1}^{t_2} dt = - \int_{0.9U_{DD}}^{0.1U_{DD}} \frac{C_L}{I_n} dU_{OUT}$$



1. n-channel-transistor in saturation:

$$I_n = \frac{\beta}{2} (U_{GS} - U_T)^2$$

2. n-channel-transistor in linear region:

$$I_n = \beta (U_{GS} - U_T - \frac{1}{2} U_{DS}) U_{DS}$$

# Discharge of capacity

1.  $\Rightarrow$  n-Kanal-Transistor in Saturation  $\Rightarrow$

$$\begin{aligned} t_{fs} &= - \int_{0.9U_{DD}}^{U_{DD}-U_T} \frac{C_L}{I_n} dU_{OUT} \\ &= \frac{C_L}{\frac{1}{2} \beta_n (U_{DD} - U_T)^2} (U_T - 0.1U_{DD}) \end{aligned}$$

2.  $\Rightarrow$  n-channel-transistor in linear range  $\Rightarrow$

$$\begin{aligned} \Rightarrow t_{fl} &= - \int_{U_{DD}-U_T}^{0.1U_{DD}} \frac{C_L}{I_n} dU_{out} \\ &= \frac{C_L}{\beta_n (U_{DD} - U_T)} \ln \left( \frac{19U_{DD} - 20U_T}{U_{DD}} \right) \end{aligned}$$

# Falling Edge

$$t_{fs} = \frac{2C_L}{\beta_n (U_{DD} - U_T)^2} (U_T - 0.1U_{DD})$$

$$t_{fl} = \frac{C_L}{\beta_n (U_{DD} - U_T)} \ln \left( \frac{19U_{DD} - 20U_T}{U_{DD}} \right)$$

---


$$\left. \begin{array}{ll} U_{DD} = 5V & U_T = 1V \\ U_{DD} = 3,3V & U_T = 0,65V \\ U_{DD} = 1,8V & U_T = 0,35V \end{array} \right\} \square U_T \approx \frac{1}{5} U_{DD}$$

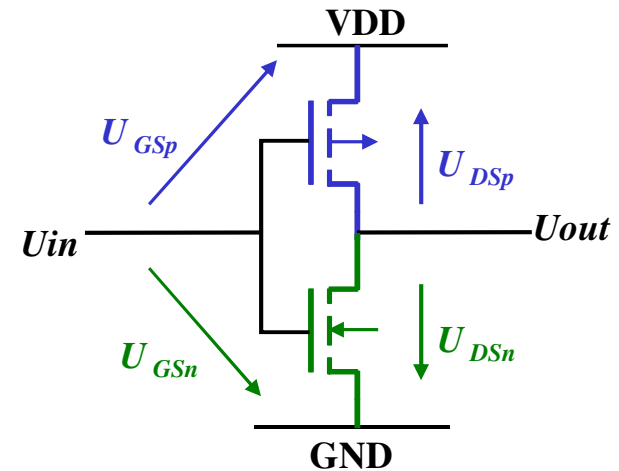
$$t_f = t_{fs} (0.9 \cdot U_{DD} \rightarrow U_{DD} - U_T) + t_{fl} (U_{DD} - U_T \rightarrow 0.1 \cdot U_{DD})$$

$$\approx \frac{0.3 \cdot C_L}{\beta_n U_{DD}} + \frac{3.4 \cdot C_L}{\beta_n U_{DD}} \approx \frac{4C_L}{\beta_n U_{DD}}$$

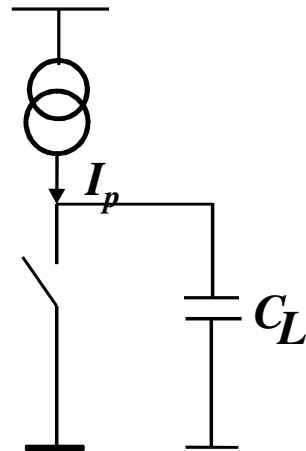
# Charging of a capacity

Falling edge:

$$t_f = t_{fl} + t_{fs} \approx \frac{4C_L}{\beta_n U_{DD}}$$



Rising Edge:



$$t_r = t_{rl} + t_{rs} \approx \frac{4C_L}{\beta_p U_{DD}}$$

For higher speed:  $C_L \downarrow$   $U_{DD} \uparrow$   $\beta \uparrow$   $\left( \beta = \frac{W}{L} \mu C'_{ox} = \frac{W}{L} \mu \frac{\epsilon_{ox}}{t_{ox}} \right)$

# Total delay times

$$t_{ges} = t_r + t_f$$

$$= \frac{4C_L}{U_{DD}\beta_n} + \frac{4C_L}{U_{DD}\beta_p}$$

$$t_{ges} = \frac{4C_L}{U_{DD}} \left( \frac{1}{\beta_n} + \frac{1}{\beta_p} \right)$$

Particularly for  $t_f = t_r$

$$\Rightarrow \beta_n = \beta_p = \beta \quad \left( = \frac{W}{L} \mu \frac{\epsilon_{ox}}{t_{ox}} \right)$$

$$t_{ges} = t_r + t_f = \frac{8C_L}{U_{DD}\beta}$$

$$\Rightarrow \text{bei } L_n = L_p, \quad \frac{W_p}{W_n} = \frac{\mu_n}{\mu_p}$$

$$\Rightarrow W_p \square 3 * W_n$$



# Delay times with inverter as load

$$t_{ges} = \frac{4C_L}{U_{DD}} \left( \frac{1}{\beta_n} + \frac{1}{\beta_p} \right)$$

$$C_{Linv} = (W_n L_n + W_p L_p) C'_{OX}$$

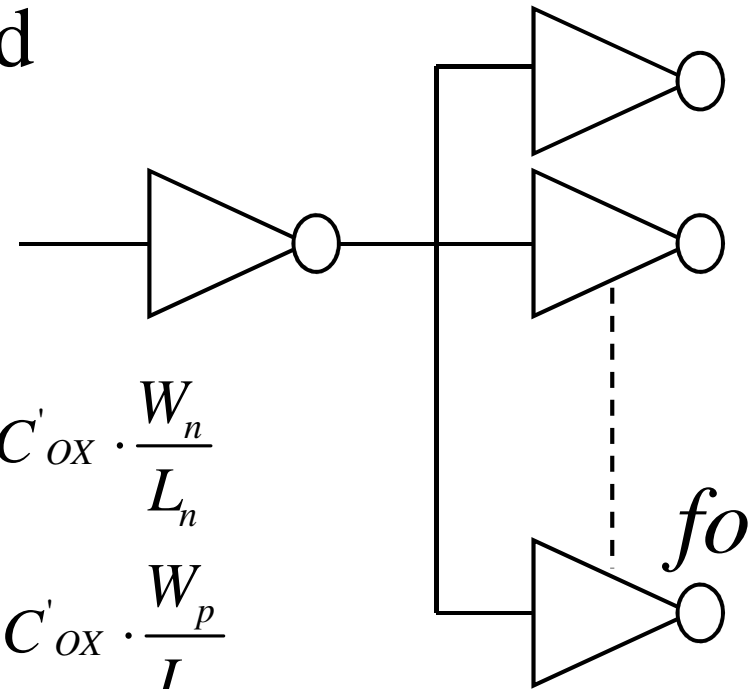
$$\beta_n = \mu_n C'_{OX} \cdot \frac{W_n}{L_n}$$

$$\beta_p = \mu_p C'_{OX} \cdot \frac{W_p}{L_p}$$

$$t_{ges} = 4 \frac{\cancel{C'_{OX}} \cdot L \cdot (W_n + W_p)}{U_{DD}} \cdot \left( \frac{L}{W_n \mu_n \cancel{C'_{OX}}} + \frac{L}{W_p \mu_p \cancel{C'_{OX}}} \right)$$

*Assumption :*

$$L_n = L_p = L$$



If  $t_r = t_f \Rightarrow W_n \mu_n = W_p \mu_p$

$$t_{ges} = 8 \frac{L^2}{U_{DD}} \cdot \left( \frac{1}{\mu_n} + \frac{1}{\mu_p} \right)$$

$fo$  (fan-out) inverters as load yield to:  $t_{ges,fo} = fo * t_{ges}$

# Minimum delay time (with inverter as load)

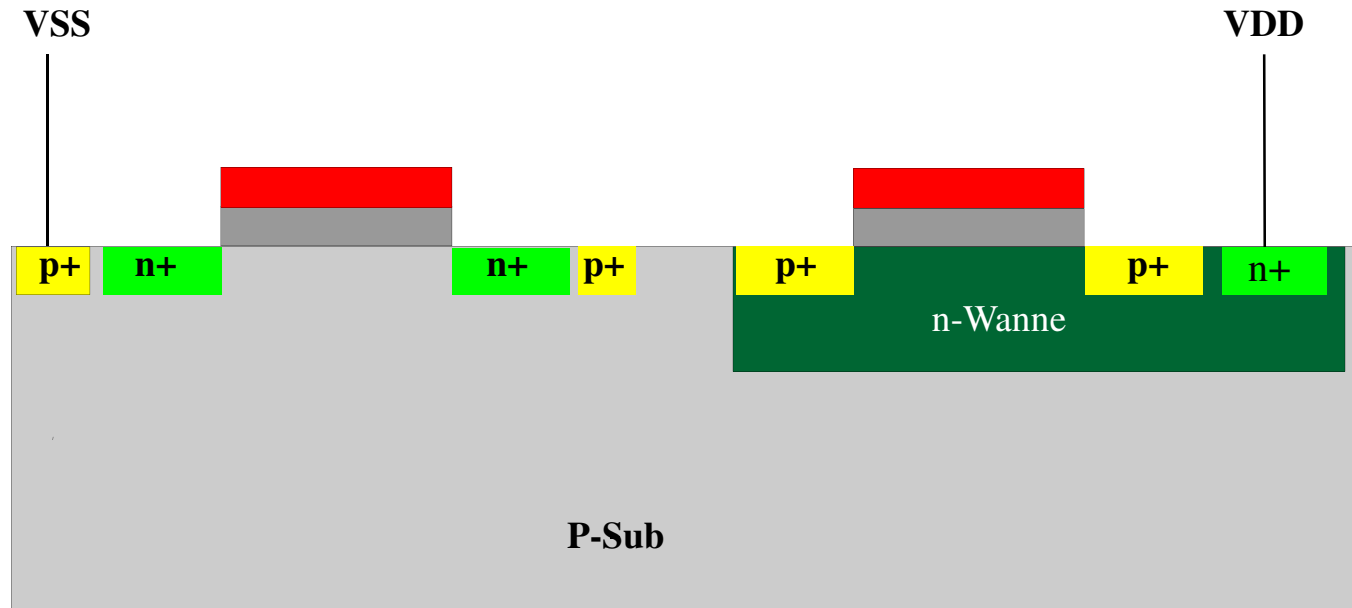
$$t_{ges} = \frac{4C_L}{U_{DD}} \left( \frac{1}{\beta_n} + \frac{1}{\beta_p} \right)$$

$$t_{ges} \text{ minimum} \Rightarrow \left. \frac{dt_{ges}}{dW_p} \right|_{W_n=const.} = 0$$

$$t_{ges} = 4 \frac{L^2 \cdot (W_n + W_p)}{U_{DD}} \cdot \left( \frac{1}{W_n \mu_n} + \frac{1}{W_p \mu_p} \right)$$

$$\text{Solution: } \frac{W_p}{W_n} = \sqrt{\frac{\mu_n}{\mu_p}}$$

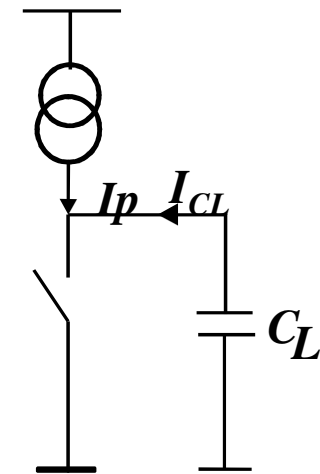
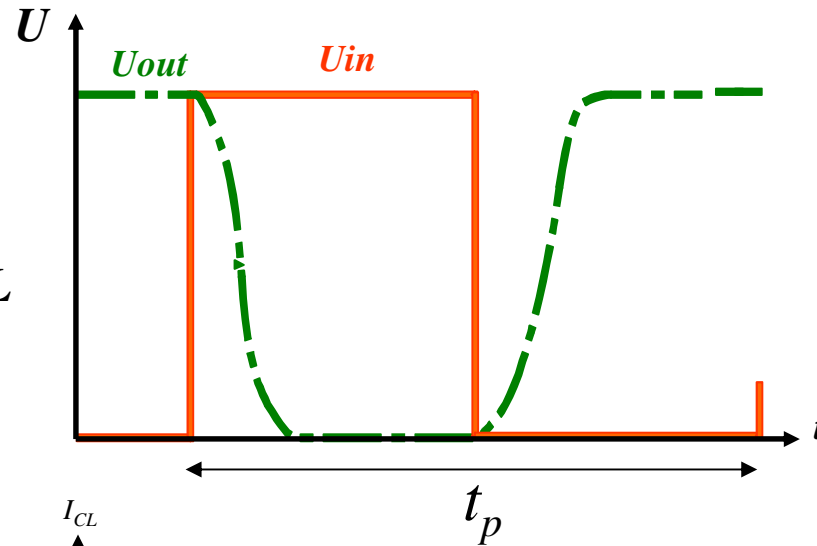
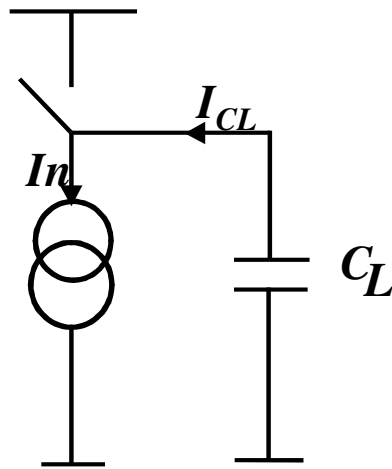
# Static power loss



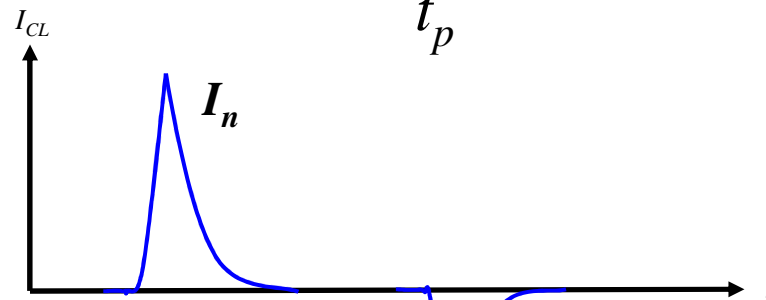
$$I_L = A \cdot I_s \left( e^{\left( \frac{U_D}{kT/q} \right)} - 1 \right) \quad I_{WI} = I_{WI0} e^{n \left( \frac{U_{GS} - U_T}{kT/q} \right)}$$

$$P = \sum_n (I_L + I_{WI}) * U_{DD}$$

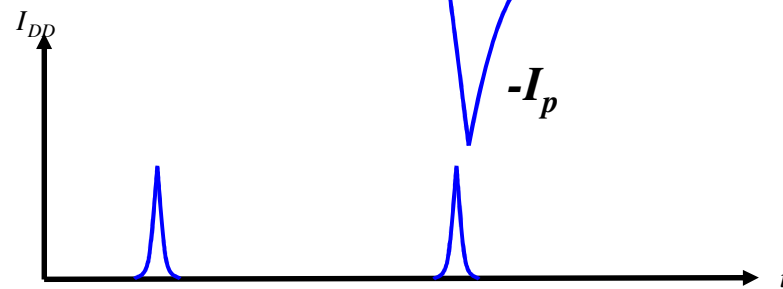
# Dynamic power loss



Charging current



Short circuit current



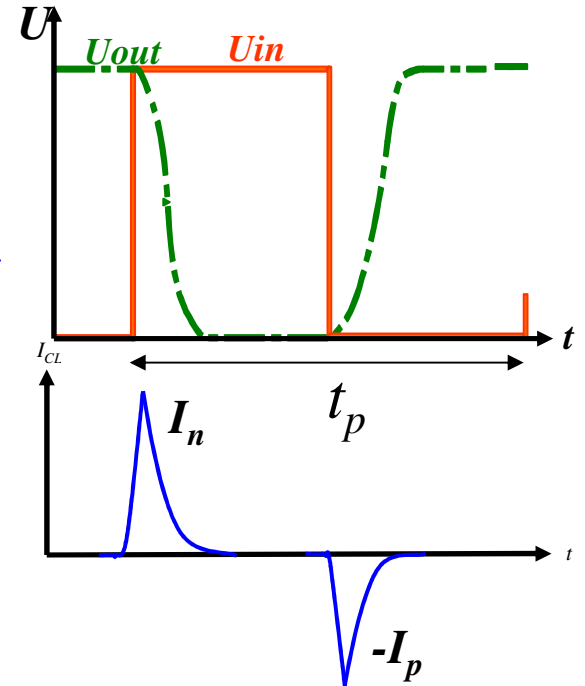
Capacity (90%)

Short circuit (9%)

Static current (1%)

# Average dynamic (C-load) power loss

$$P = \frac{1}{t_p} \left[ \int_0^{t_p} I(t) \cdot U_{out}(t) dt \right] \quad \begin{aligned} i_n(t) &= -C_L \frac{dU_{out}}{dt} \\ i_p(t) &= -C_L \frac{d(U_{DD} - U_{out})}{dt} \end{aligned}$$



$$P = \frac{1}{t_p} \left[ \int_0^{t_r} i_p(t) \cdot (U_{DD} - U_{out}(t)) dt + \int_0^{t_f} i_n(t) \cdot U_{out}(t) dt \right]$$

$$P = \frac{1}{t_p} \left[ \int_0^{U_{DD}} -C_L (U_{DD} - U_{out}) d(U_{DD} - U_{out}) + \int_{U_{DD}}^0 -C_L U_{out} dU_{out} \right]$$

---


$$P = I \cdot U_{DD} = \frac{Q}{t_p} \cdot U_{DD} = \frac{C_L \cdot U_{DD}}{t_p} \cdot U_{DD} = \frac{C_L \cdot U_{DD}^2}{t_p} = f \cdot C_L \cdot U_{DD}^2$$

# Power loss $\Leftrightarrow$ Speed

$$P = \frac{C_L \cdot U_{DD}^2}{t_p} = f \cdot C_L \cdot U_{DD}^2$$

For low power circuitry:  $f \downarrow$   $C_L \downarrow$   $U_{DD} \downarrow$

$$t_{ges} = \frac{4C_L}{U_{DD}} \left( \frac{1}{\beta_n} + \frac{1}{\beta_p} \right)$$

For high speed circuitry:  $U_{DD} \uparrow$   $C_L \downarrow$   $\beta \uparrow$

Example: a symetric inverter as load

$$t_{ges} = 8 \frac{L^2}{U_{DD}} \cdot \left( \frac{1}{\mu_n} + \frac{1}{\mu_p} \right) \quad U_{DD} \uparrow \quad L \downarrow \quad (temp \downarrow)$$

Low Power and High Speed is contradiction.

# Chapter 5

- Design rules
- Standard cell layout
- Scaling

## Design Rules (Layout Design Rules)

### Why Design Rules

- fabrication process has minimum/maximum feature sizes that can be produced for each layer
- alignment between layers requires adequate separation (if layers unconnected) or overlap (if layers connected)
- proper device operation requires adequate separation

### Basic Rules

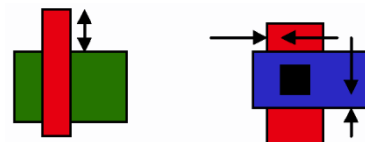
Minimum width



Minimum distance



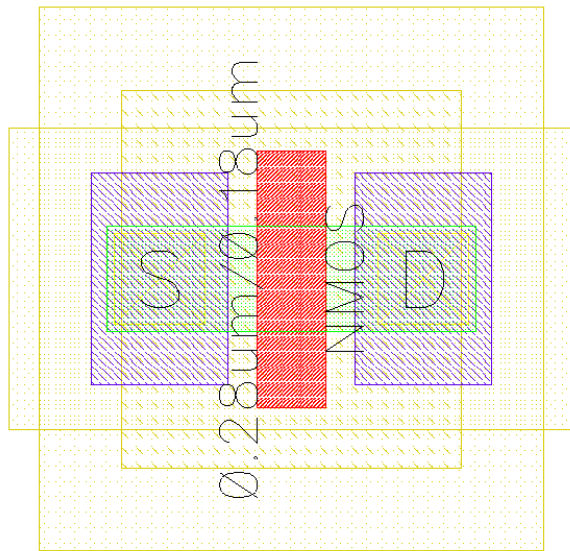
Minimum overlap



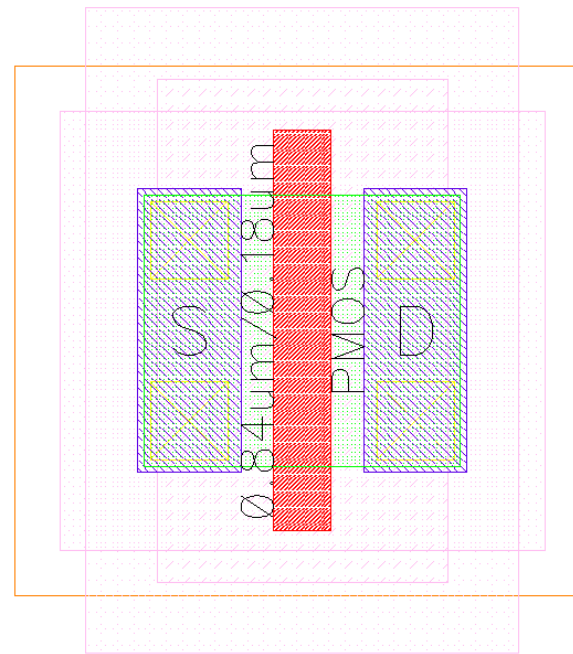


## Hierarchically Layout

|                  |    |                   |
|------------------|----|-------------------|
| Polygom          | -> | Transistor (cell) |
| Transistor       | -> | Gate (cell)       |
| Gate             | -> | Logical function  |
| Logical function | -> | Complex function  |
| Complex function | -> | Chip Top Level    |

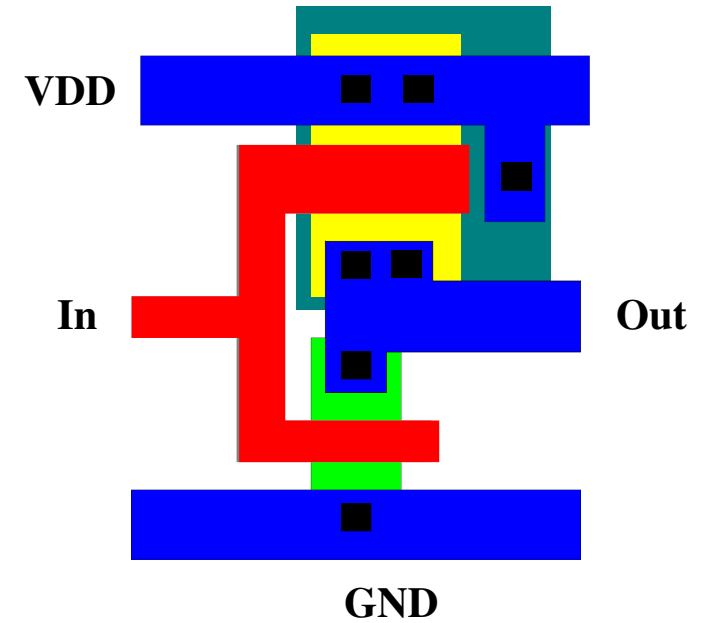
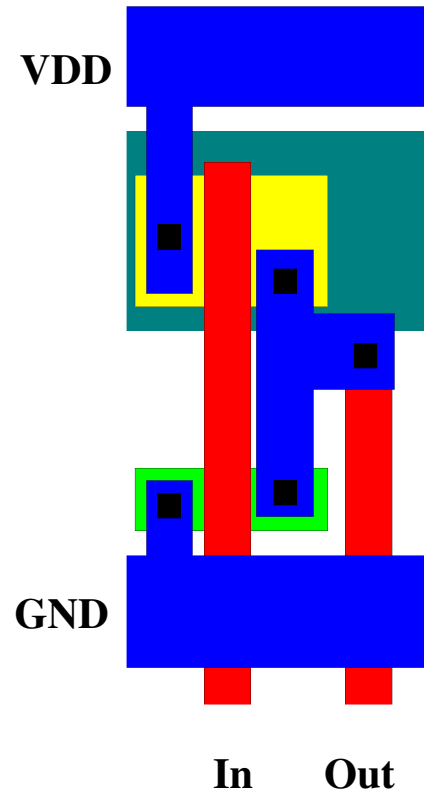
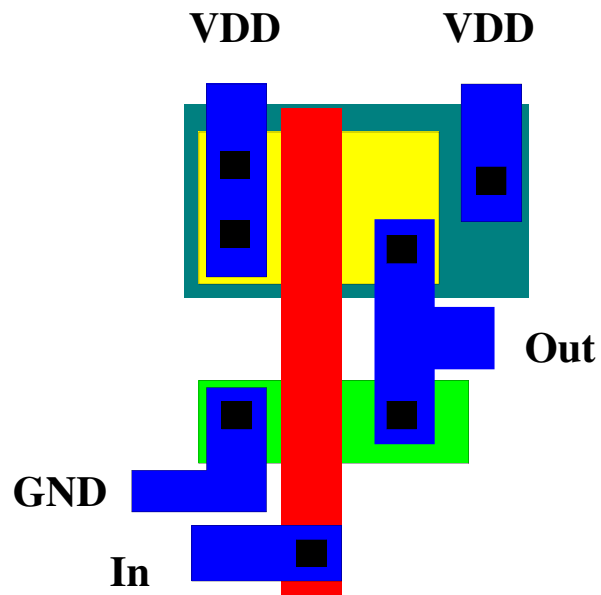


*NMOS 0.28/0.18*



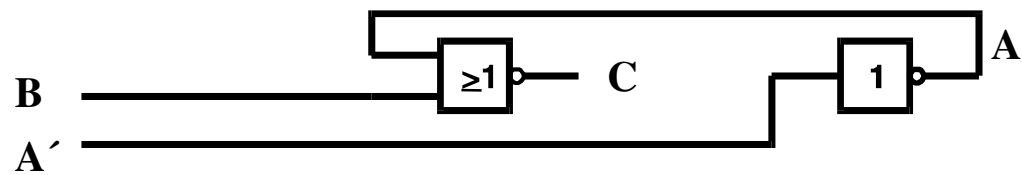
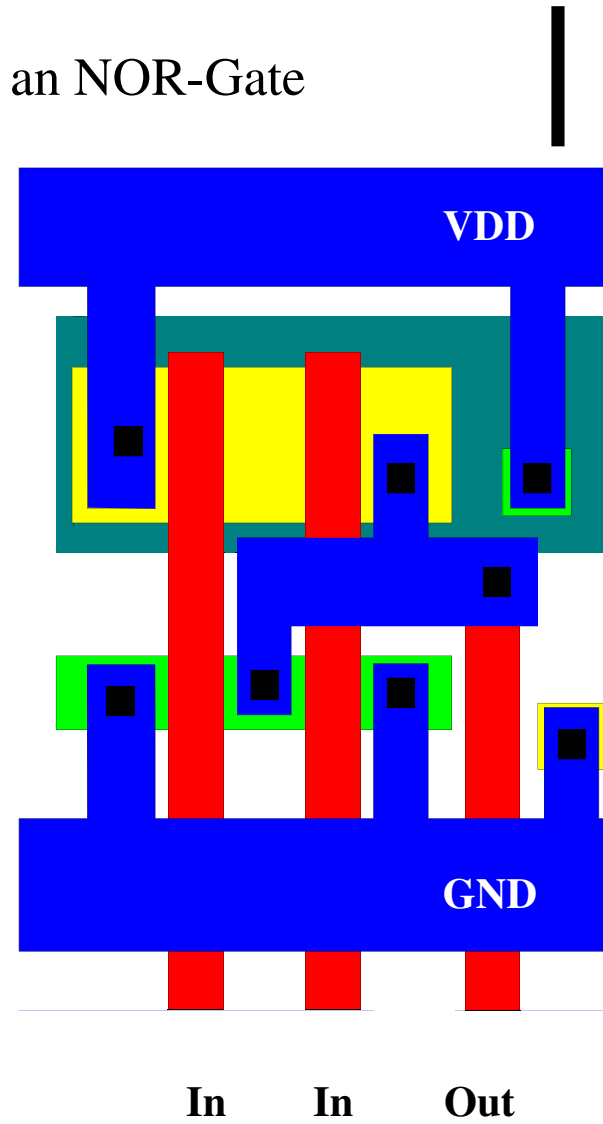
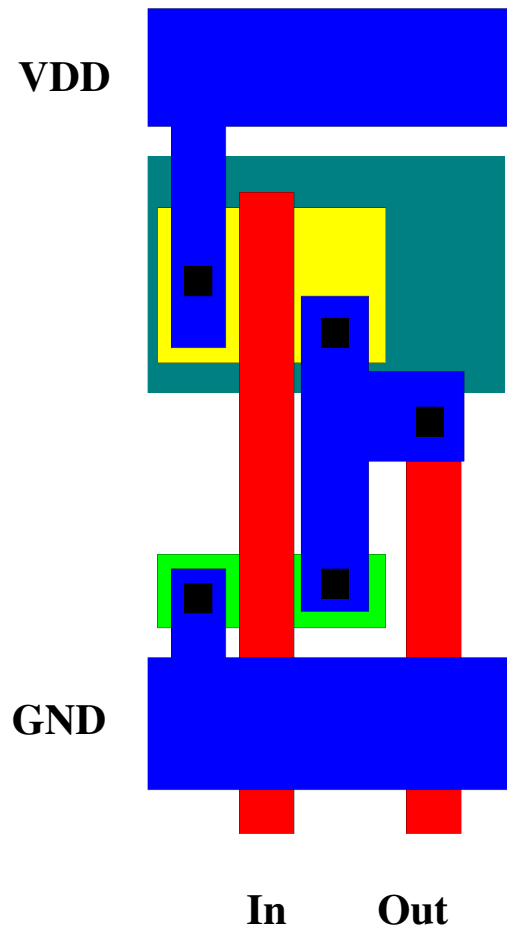
*PMOS 0.84/0.18*

# Inverter Layouts

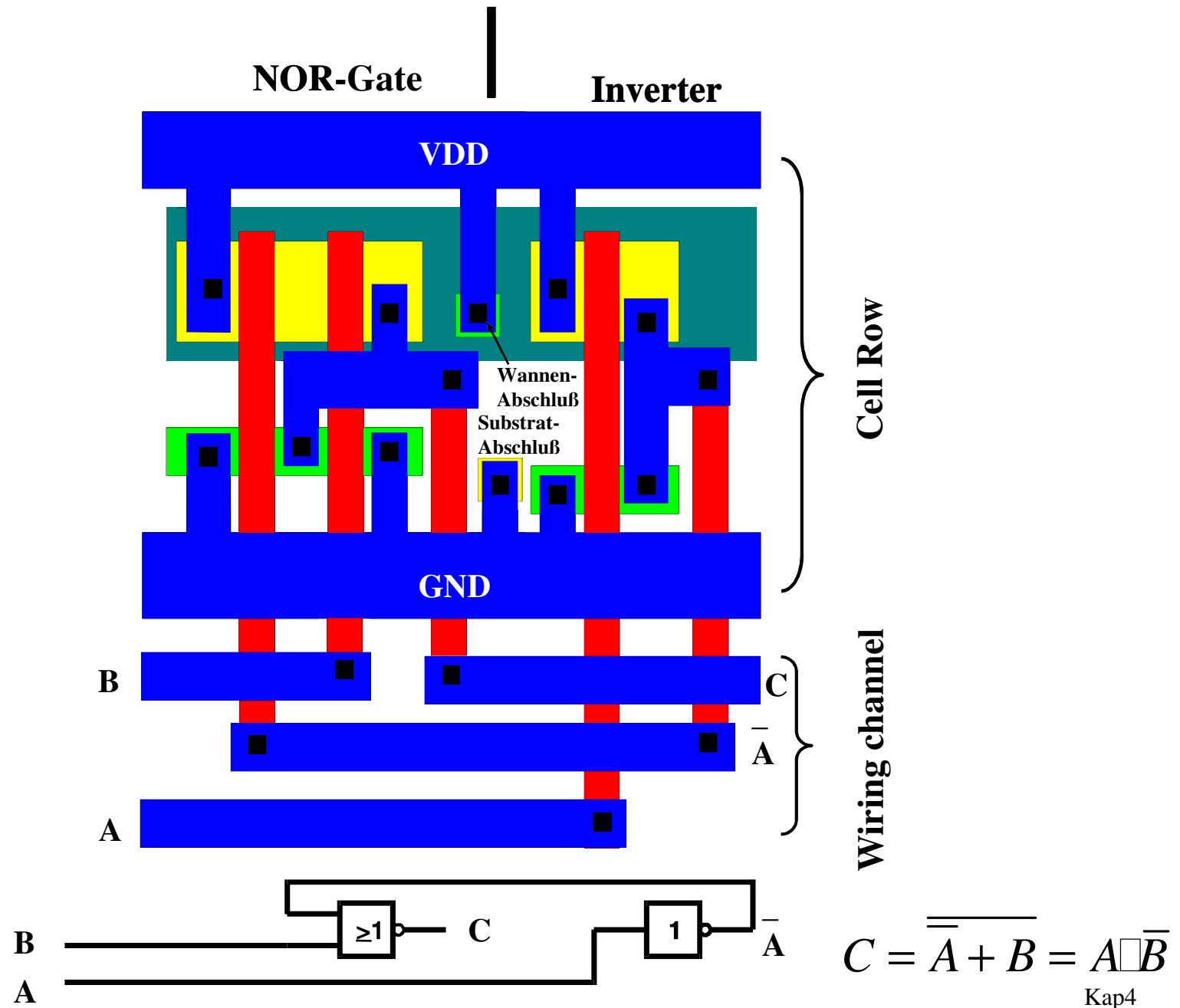


- Metall
- n-Diffusion
- p-Diffusion
- Polysilicon
- n-basin

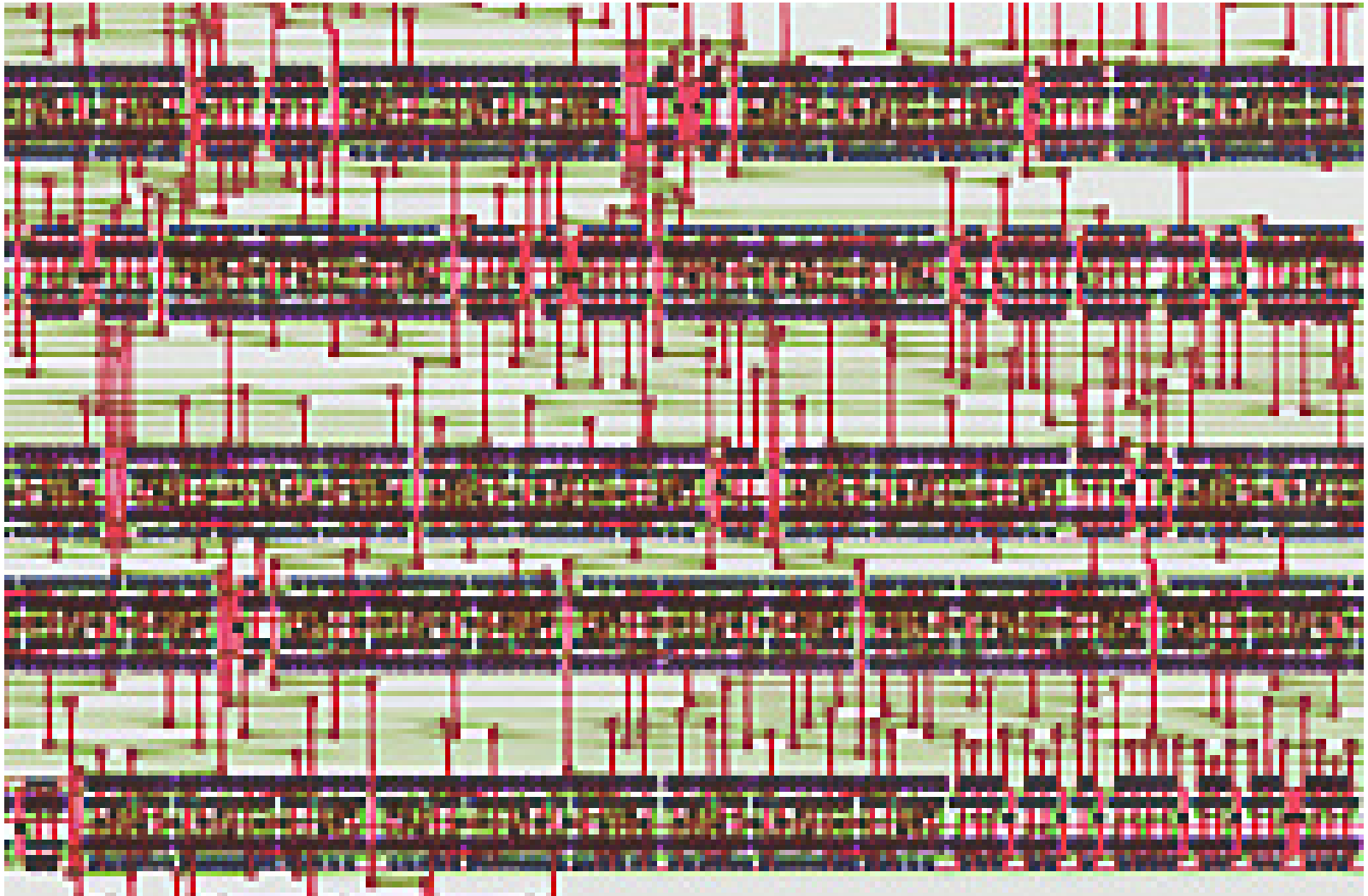
# Layout of an NOR-Gate



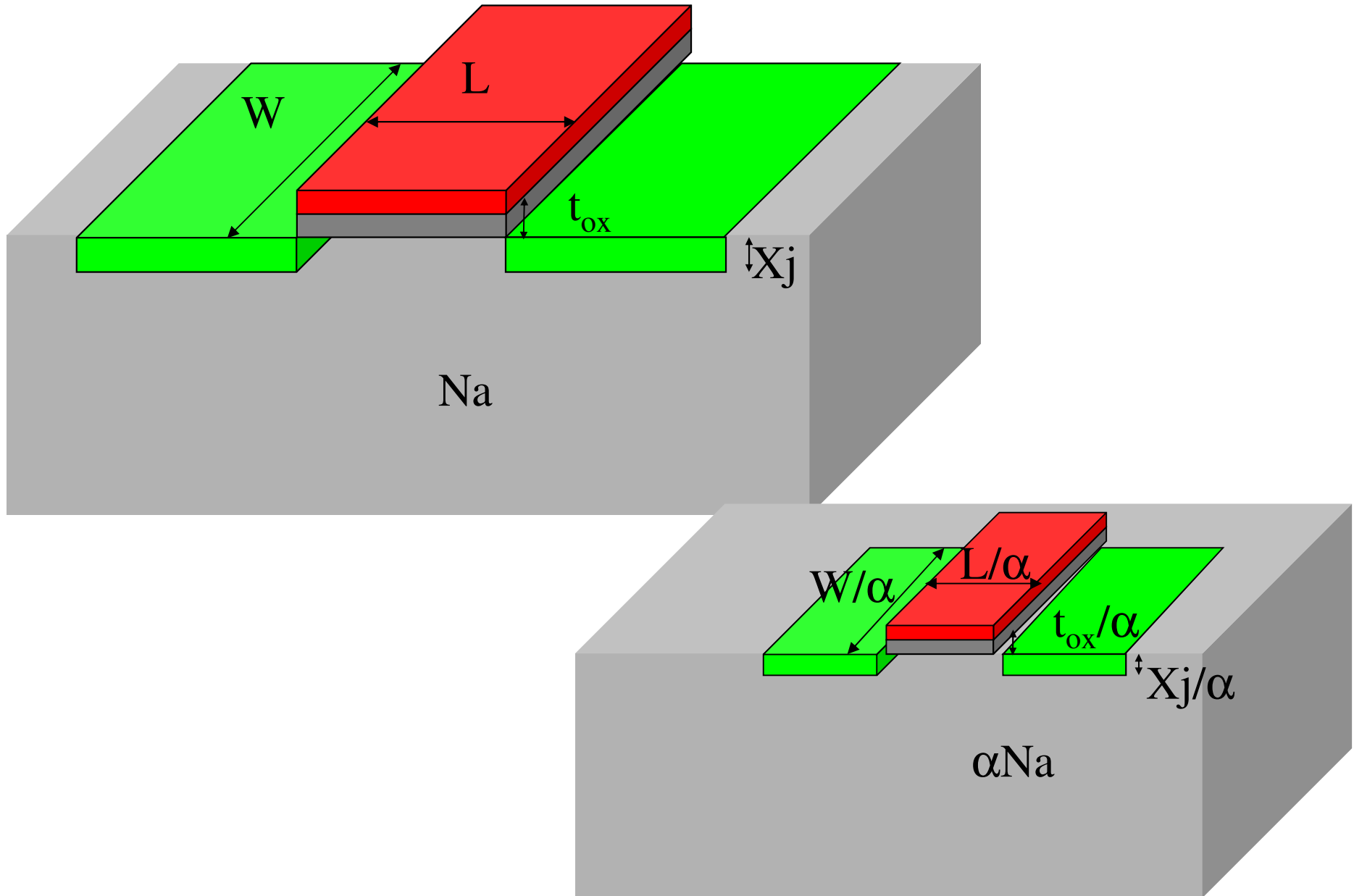
# Layout of a circuit of inverter and NOR

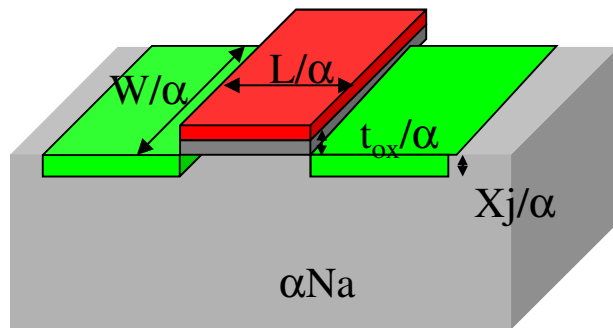


# Block Layout



## Scaling of processes by a factor $\alpha$





| Scaling with constant                       | Voltage                           | Field                   |
|---|-----------------------------------|-------------------------|
| Channel length $L$                          | $1/\alpha$                        | $1/\alpha$              |
| Channel width $W$                           | $1/\alpha$                        | $1/\alpha$              |
| Area $A=W * L$                              | $1/\alpha^2$                      | $1/\alpha^2$            |
| Oxide thickness $t_{ox}$                    | $1/\alpha$                        | $1/\alpha$              |
| Power supply $U_{DD}$                       | 1                                 | $1/\alpha$              |
| Beta $\beta=\mu(W/L)(\epsilon_{ox}/t_{ox})$ | $\alpha$                          | $\alpha$                |
| Current $I=1/2\beta(U_{GS}-U_T)^2$          | $\alpha$                          | $1/\alpha$              |
| Gate capacity $W*L* \epsilon_{ox}/t_{ox}$   | $1/\alpha$                        | $1/\alpha$              |
| Delay time $t_{f,r}=4C_L/\beta*U_{DD}$      | $1/\alpha^2$<br>( $C_L/ \alpha$ ) | $1/\alpha$<br>( $C_L$ ) |
| Clock rate $f=1/T$                          | $\alpha^2$                        | $\alpha$                |
| Dyn. power loss $P_d=f*C_L*U_{DD}^2$        | $\alpha$                          | $1/\alpha^2$            |
| Current density $J=I/A$                     | $\alpha^3$                        | $\alpha$                |
| Power density $P/A$                         | $\alpha^3$                        | 1                       |

The elctrical field will be maintained constant

## Example of modern CMOS processes

| Technology            | 0.18um               | 0.15um               | 0.13um                     | 90nm                 |
|-----------------------|----------------------|----------------------|----------------------------|----------------------|
| Production Start      | 1Q99                 | 1Q00                 | 1Q01                       | 3Q02                 |
| Core Vdd              | 1.5V-1.8V            | 1.2-1.5V             | 1.0-1.5V                   | 1.0-1.2V             |
| IO Vdd                | 2.5V, 3.3V           | 2.5V, 3.3V           | 2.5V, 3.3V                 | 1.8V-3.3V            |
| Poly Half-pitch       | 0.215um              | 0.185um              | 0.155um                    | 0.12um               |
| Gate Length(Physical) | 0.16-0.13um          | 0.11-0.12um          | 0.08-0.085um               | 45-80nm              |
| Gate Dielectric (EOT) |                      |                      |                            |                      |
| - Core                | 26A, 32A             | 20A, 26A             | 16-26A                     | 13-22A               |
| - I/O, Analog Option  | 50A, 70A             | 50A, 70A             | 50A, 70A                   | 28A-70A              |
| Metal Layers          | 6 Al                 | 7 Al or Cu           | 7 - 8 Cu                   | 9 - 10 Cu            |
| BEOL Dielectric (k)   | Low k (3.6)          | Low-k (3.6)          | Low-k (2.9, 3.6)           | Low-k (2.9, <2.5)    |
| Contacted M1 Pitch    | 0.46um               | 0.39um               | 0.34 um                    | 0.24um               |
| Contacted Mx Pitch    | 0.56um               | 0.48um               | 0.41 um                    | 0.28um               |
| Top Metal Pitch (std) | 0.9um                | 0.9um                | 0.9 um                     | 0.84um               |
| Emb-6T SRAM Cell      | 4.65 um <sup>2</sup> | 3.42 um <sup>2</sup> | 2.43, 2.14 um <sup>2</sup> | 1.27 um <sup>2</sup> |
| Design Rules/SPICE    | Available            | Available            | Available                  | Available            |

Source: TSMC, 2003